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Li-Da Huang, Martin D. F. Wong

June 2004 **Proceedings of the 41st annual conference on Design automation**

Publisher: ACM Press

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As the technology migrates into the deep submicron manufacturing(DSM) era, the critical dimension of the circuits is getting smaller than the lithographic wavelength. The unavoidable light diffraction phenomena in the sub-wavelength technologies have become one of the major factors in the yield rate. Optical proximity correction (OPC) is one of the methods adopted to compensate for the light diffraction effect as a post layout process. However, the process is time-consuming and the results are st ...

**Keywords:** OPC, VLSI, manufacturing, maze routing, micro-lithography, optical system

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Andrew B. Kahng, Y. C. Pati

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A. B. Kahng, Y. C. Pati

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Franklin M. Schellenberg, Luigi Capodiec

April 2001 **Proceedings of the 2001 international symposium on Physical design**

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